

IN THE CLAIMS:

1. (amended) An apparatus for inspecting a reflective EUV mask blank for defects, comprising:

an EUV light source; and

means for simultaneously imaging multiple points in an area of a mask blank in response to reflections of light from said EUV light source impinging on said mask blank.

7. (amended) An apparatus for inspecting a reflective EUV mask blank for defects, comprising:

means for directing EUV light to a mask blank; and

means for simultaneously imaging multiple points of an area of a mask blank in response to reflections of EUV light impinging on said mask blank.

13. (amended) An apparatus for inspecting a reflective EUV mask blank for defects, comprising:

an EUV light source configured to direct a beam of light toward a mask blank;

and

an EUV detector configured to simultaneously image multiple points of an area of said mask blank in response to light from said EUV light source reflected from said area of said mask blank to be imaged.

defects, comprising simultaneously imaging multiple points of an area of a mask blank

in response to reflections of light from an EUV light source impinging on said mask blank.

29. (amended) A method for inspecting a reflective EUV mask blank for defects, comprising:

directing a beam of light from an EUV light source toward a mask blank; and  
simultaneously imaging multiple points of an area of said mask blank in  
response to light from said EUV light source reflected from said area of said mask blank  
to be imaged.